

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Ap	oplication of:)	
		:	Examiner: NYA
HARU	HITO ONO ET AL.)	
		:	Group Art Unit: NYA
Applica	ation No.: 10/615,955)	
		:	
Filed: July 10, 2003)	
		:	
For:	MULTI-CHARGED BEAM LENS,)	
	CHARGED-PARTICLE BEAM	:	
	EXPOSURE APPARATUS USING)	
	THE SAME, AND DEVICE	:	
	MANUFACTURING METHOD)	September 2, 2003
Mail St	op		
	ssioner for Patents		
P.O. Bo	ox 1450		

<u>INFORMATION DISCLOSURE STATEMENT</u>

Sir:

Alexandria, VA 22313-1450

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed Form PTO-1449. Copies of the listed documents are also enclosed.

CONCLUSION

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

Attorney for Applicants

Registration No.

FITZPATRICK, CELLA, HARPER & SCINTO 30 Rockefeller Plaza

New York, New York 10112-3801 Facsimile: (212) 218-2200

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FORM PTO 1449 (modified)			ATTY DOCKET NO. APPLICATION NO. 10/615,955						
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE PE			APPLICABLE						
	RENCES CITED BY AP		MANUNITO DINO ET AL.						
		aly) •	FILING DATE		GROUP				
Date Submitted to PTO:[DATE] SEP 0 3 2003		JULY 10, 2003		NYA					
	\		U.S. PATENT DOCUMENTS						
*EXAMINER INITIAL	DOCUMENT NUMBER	TRADEMAN	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE			
- . 									
			FOREIGN PATENT DOCUMEN	TS					
	DOCUMENT	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT			
	NUMBER					ON ABSTRACT			
	1								
	1					 			
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)									
T. Sasaki, A Multibeam Scheme for Electron-Beam Lithography, J. Vac. Sci. Technol., 19(4), Nov./Dec. 1981, pp. 963-965									
	K.Y. Lee et al., <i>High Aspect Ratio Aligned Multilayer Microstructure Fabrication</i> , J. Vac. Sci, Technol. B 12(6), Nov/Dec 1994, pp. 3425-3431								
	A.D. Feiner	A.D. Feinerman, et al., Sub-centimeter Micromachined Electron Microscope, J. Vac. Sci. Technol. A 10(4), July/Aug 1992, pp 611-616							
EXAMINER			DATE CONSIDERED						

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.